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METHOD AND SYSTEM FOR CALIBRATING THE SCAN
AMPLITUDE OF AN ELECTRON BEAM LITHOGRAPHY INSTRUMENT

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ABSTRACT OF THE DISCLOSURE

A method for calibrating the scan amplitude of an electron beam lithography instrument by determining the position of a feature within the scan. The method is effective at the operating frequency of the scan and using a limited bandwidth video signal including the steps of determining the reference feature to be an edge over which the video signal rises abruptly from a background level to a white level. The method turns the beam on only over a short region of the scan and represents the degree of overlap between the beam on portion of the scan and the white part of the feature as the total video signal accumulated in that scan.

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